

IN THE CLAIMS

1. (Currently Amended) A gas distribution apparatus for supplying gas into a semiconductor wafer processing chamber, the apparatus comprising:

a body having a bottom wall and a plurality of gas inlets ~~extending through that~~ perforate the bottom wall; and

an injection plate ~~to be screwed with the bottom part of the body, attached to a bottom surface of the bottom wall, the injection plate having small and large diameters of ring-shaped grooves on its~~ an upper surface of the injection plate that ~~to connect the gas inducing inlets, the injection plate also having grooves having injection holes that perforate the injection plate formed at a predetermined interval for downward penetration at predetermined intervals throughout the grooves.~~

2. (Currently Amended) The apparatus, as defined in claim 1, wherein the gas ~~inducing~~ inlets are formed at different distances from ~~the~~ a center of the bottom ~~part of the~~ body wall.

3. (Currently Amended) The apparatus, as defined in claim 1, wherein the body additionally comprises a plurality of gas inlet extensions that are integral to the bottom wall such that the gas inducing inlets ~~upwardly protrude~~ protrude upwardly from the ~~body~~ bottom wall.

4. (Currently Amended) The apparatus, as defined in claim 1, wherein ~~the~~ an external periphery of ~~the~~ an upper portion of the body is fastened to the chamber.

5. (Currently Amended) The apparatus, as defined in claim 1, wherein ~~the body includes the gas inducing inlets with a vertically extended diameter for downward penetration~~ the grooves include a ring-shaped groove with a large diameter and a ring-shaped groove with a small diameter.

6. (Currently Amended) The apparatus, as defined in claim 1, wherein the injection plate is ~~fastened with the bottom part of its external periphery~~ attached to the bottom ~~surface of the body~~ wall with a plurality of screws.

7. (Currently Amended) A gas distribution apparatus of semiconductor equipment to supply gas into a chamber for a plasma etching process, the apparatus comprising:

a body having a plurality of gas ~~inducing~~ inlets that perforate the body and a cooling water path configured to circulate cooling water inside the body ~~means on a downward grooved side of its plate~~; and

an injection plate attached to ~~the~~ a bottom surface of the body, the injection plate having ~~small and large diameter ring-shaped grooves on its~~ an upper surface ~~to~~ with grooves that connect the gas inducing inlets, the injection plate also the grooves having injection holes that perforate the injection plate formed at a ~~at~~ predetermined interval for downward penetration intervals inside the grooves.

8. (Currently Amended) The apparatus, as defined in claim 7, wherein the gas ~~inducing~~ inlets are formed at different ~~diameters~~ distances from the center of ~~the~~ a bottom part of the body.

9. (Currently Amended) The apparatus, as defined in claim 7, wherein the body additionally comprises a plurality of gas inlet extensions that are integral to the body such that the gas inducing inlets are upward protruded protrude upward from the body.

10. (Currently Amended) The apparatus, as defined in claim 7, wherein ~~the~~ an external periphery of ~~the~~ an upper portion of the body is fastened to the chamber.

11. (Currently Amended) The apparatus, as defined in claim 7, wherein the ~~body has the gas inducing inlets with a vertically extended diameter for downward penetration.~~ grooves include a ring-shaped groove with a large diameter and a ring-shaped groove with a small diameter.

12. (Currently Amended) The apparatus, as defined in claim 7, wherein the injection plate is ~~fastened with the bottom part of its external periphery~~ attached to the bottom surface ~~of the body~~ with a plurality of screws.

13. (Currently Amended) The apparatus, as defined in claim 7, wherein the cooling ~~means~~ water path includes an injecting hole and a discharging ~~holes~~ hole ~~for inducing~~

~~and discharging cooling water and a cooling water path connecting the injecting and discharging holes for circulating cooling water in the body.~~

14. (Currently Amended) The apparatus, as defined in claim 13, wherein the injecting and discharging holes ~~are upwardly protruded~~ protrude upwardly from the bottom part of the body.